

# Pseudo uridine penta-tms

|                             |  |
|-----------------------------|--|
| <b>Other names:</b>         | «beta»-Pseudouridine, TMS  |
| <b>Inchi:</b>               | InChI=1S/C24H52N2O6Si5/c1-33(2,3)27-17-19-21(29-34(4,5)6)22(30-35(7,8)9)20(28-19 |
| <b>InchiKey:</b>            | XHLZQKAETJELAB-UHFFFAOYSA-N  |
| <b>Formula:</b>             | C24H52N2O6Si5  |
| <b>SMILES:</b>              | C[Si](C)(C)OCC1OC(c2cnc(O[Si](C)(C)C)nc2O[Si](C)(C)C)C(O[Si](C)(C)C)C1O[Si](C)(C |
| <b>Mol. weight [g/mol]:</b> | 605.11   |
| <b>CAS:</b>                 | 53294-25-0   |

## Physical Properties

| Property code | Value   | Unit | Source         |
|---------------|---------|------|----------------|
| log10ws       | 3.96    |      | Crippen Method |
| logp          | 6.636   |      | Crippen Method |
| rinpola       | 2375.00 |      | NIST Webbook   |
| rinpola       | 2375.00 |      | NIST Webbook   |

## Sources

|                        |   |
|------------------------|---|
| <b>Crippen Method:</b> | <a href="http://pubs.acs.org/doi/abs/10.1021/ci9903071">http://pubs.acs.org/doi/abs/10.1021/ci9903071</a>                                     |
| <b>Crippen Method:</b> | <a href="https://www.chemeo.com/doc/models/crippen_log10ws">https://www.chemeo.com/doc/models/crippen_log10ws</a>                             |
| <b>NIST Webbook:</b>   | <a href="http://webbook.nist.gov/cgi/cbook.cgi?ID=C53294250&amp;Units=SI">http://webbook.nist.gov/cgi/cbook.cgi?ID=C53294250&amp;Units=SI</a> |

## Legend

|                 |                                     |
|-----------------|-------------------------------------|
| <b>log10ws:</b> | Log10 of Water solubility in mol/l  |
| <b>logp:</b>    | Octanol/Water partition coefficient |
| <b>rinpola:</b> | Non-polar retention indices         |

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